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SECTION 2: FORM PTO 1449 - MODIFIED

 1c973 U.S. PTO
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Hardjono, T. P. Atty Dkt: 2204/A82

Serial No: --- Examiner: ---

Date Filed: --- Group No:

Invention: Spatial Key Trees for Key Management in Wireless Environments

Commissioner for Patents
 Washington, DC 20231

LIST OF PATENTS AND PUBLICATIONS FOR APPLICANTS'
 INFORMATION DISCLOSURE STATEMENT

U.S. PATENT DOCUMENTS

<u>Exam</u> <u>Init.</u>	<u>Ref.</u> <u>No.</u>	<u>Document</u> <u>Number</u>	<u>Date</u>	<u>Name</u>	<u>Class</u>
<i>JK</i>	AA	6,049,878	04/11/00	Caronni, et al	713/201
<i>h</i>	AB	5,748,736	05/05/98	Mittra	380/21

OTHER PUBLICATIONS

<u>Exam.</u> <u>Init.</u>	<u>Ref.</u> <u>No.</u>	
<i>JK</i>	AC	Briscoe, Bob, "MARKS: Zero Side Effect Multicast Key Management using Arbitrarily Revealed Key Sequences", in <i>First International Workshop on Networked Group Communication</i> (Nov. 1999).
<i>JK</i>	AD	Hardjono, T., et al, "A Framework for Group Key Management for Multicast Security", <draft - ieff - ipsec - gkm framework - 03.txt>, August 2000.
<i>JK</i>	AE	McGrew, David A., et al, "Key Establishment in Large Dynamic Groups Using One-Way Function Trees", TIS Report No. 0755, TIS Labs at Network Associates, Inc., Glenwood, Md (May 1998).

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<u>Exam.</u> <u>Init.</u>	<u>Ref.</u> <u>No.</u>	
<u>AK</u>	AF	Rodeh, Ohad, et al, "Using AVL Trees for Fault Tolerant Group Key Management", manuscript, October 2000.
<u>W</u>	AG	Wallner, D., et al, "Key Management for Multicast: Issues and Architectures", RFC2627, July 1997.
<u>W</u>	AH	Wong, Chung Kei, et al, "Secure Group Communications Using Key Graphs", WGL98, in <i>Proceedings of SIGCOMM'98</i> , September 1998.

Examiner: [Signature]
Date Considered: 9/25/04

*NOTE

FOR EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance AND not considered. Include copy of this form with next communication to applicant.